Process Control Technologies and Their Applications in Industry

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Message from the Guest Editor

Advanced control technologies have revolutionized several industrial sectors by enabling enhanced process optimization, increased efficiency, and improved product quality. This Special Issue delves into the latest developments in advanced control technologies and their wide-ranging applications in different industries. This field encompasses a diverse range of methodologies, from model predictive control (MPC) and adaptive control to advanced optimization algorithms and machine learning-based control systems.

Overall, the goal of this Special Issue is to showcase the latest advancements in control technologies and their diverse applications across different industries. Whether your research focuses on model predictive control, adaptive control, optimization algorithms, or machine learning-based control systems, we encourage you to share your valuable insights and findings.

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Message from the Editor-in-Chief

Processes (ISSN 2227-9717) provides an advanced forum for process/system-related research in chemistry, biology, material, energy, environment, food, pharmaceutical, manufacturing and allied engineering fields. The journal publishes regular research papers, communications, letters, short notes and reviews. Our aim is to encourage researchers to publish their experimental, theoretical and computational results in as much detail as necessary. There is no restriction on paper length or number of figures and tables.

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